

2. A heater device according to claim 1, wherein said heater consists of a ceramic heater.
3. A heater device according to claim 2, wherein an electrode for radio frequency power is buried in said ceramic heater.
4. A heater device according to claim 3, wherein said ceramic plate has a thickness of no more than 2 mm.
5. A heater device according to claim 1, wherein an electrode for radio frequency power is buried in said ceramic plate.
6. A heater device according to claim 5, wherein said ceramic plate has a thickness of no more than 5 mm.
7. A heater device according to claim 1, wherein said ceramic plate is made of ceramic material essentially consisting of aluminum nitride or magnesia.
8. A heater device according to claim 1, wherein said ceramic plate further comprises an annular low wall surrounding said upper supporting surface.
9. A film forming device, comprising:  
a process vessel defining a process chamber;  
a heater defining a heating surface, said heater being placed in said process chamber;  
and  
a ceramic plate simply detachably placed on said heating surface of said heater without being fastened thereto so as to substantially entirely cover said heating surface and defining a supporting surface for supporting an object of a film forming process.
10. A heater device according to claim 1, wherein said ceramic plate is made of ceramic material essentially consisting of alumina.
11. A film forming device according to claim 9, wherein said heater consists of a ceramic heater.

12. A film forming device according to claim 9, wherein an electrode for radio frequency power is buried in said ceramic heater.

13. A film forming device according to claim 9, wherein said ceramic plate has a thickness of no more than 2 mm.

14. A film forming device according to claim 9, wherein an electrode for radio frequency power is buried in said ceramic plate.

15. A film forming device according to claim 9, wherein said ceramic plate has a thickness of no more than 5 mm.

16. A film forming device according to claim 9, wherein said ceramic plate is made of ceramic material essentially consisting of aluminum nitride or magnesia.

17. A film forming device according to claim 9, wherein said ceramic plate further comprises an annular low wall surrounding said supporting surface.

18. A heater device according to claim 1, wherein said ceramic plate is made of ceramic material essentially consisting of alumina.

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